International Application No.: PCT/JP2005/002896

U.S. Patent Application No.: Unknown

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REMARKS

Claims 15-34 are pending in this application. By this Preliminary Amendment,

Applicant AMENDS the specification and the abstract of the disclosure, CANCELS

claims 1-14 and ADDS new claims 15-34.

Applicant has attached hereto a Substitute Specification in order to make

corrections of minor informalities contained in the originally filed specification.

Applicant's undersigned representative hereby declares and states that the Substitute

Specification filed concurrently herewith does not add any new matter whatsoever to the

above-identified patent application. Accordingly, entry and consideration of the

Substitute Specification are respectfully requested.

The changes to the specification have been made to correct minor informalities

to facilitate examination of the present application.

Applicant respectfully submits that this application is in condition for allowance.

Favorable consideration and prompt allowance are respectfully solicited.

Respectfully submitted,

Date: September 19, 2005

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DESCRIPTION

1

Attorney Docket No. 36856.1372

BRANCHING FILTER AND SURFACE ACOUSTIC WAVE FILTER Technical Field

Background of the Invention

1. Field of the Invention

The present invention relates a branching filter emposed of including a first filter and second filter, which have different passbands from each other and which are connected to each other, and a surface acoustic wave device used in the branching filter, and more particularly, relates to a branching filter with the structure to improve having improved temperature properties and a surface acoustic wave device used in the branching filter.

Background Art

- Heretofore, in

2. Description of the Related Art

In communication apparatuses such as a mobile phone, a branching filter composed of including a first filter and a second filter has been widely used, the. The first filter and the second filter having have different passbands from each other and beingare connected to each other. For example, in the following patent document 1 Japanese

Unexamined Patent Application Publication No. 5-167388, a branching filter having a circuit structure shown in Fig. 17 has been is disclosed.

In a branching filter 101, a first filter 103 and a second filter 104 are connected to an input terminal 102. The first filter 103 has includes a series arm resonator S_{01} and a parallel arm resonator P_{01} , and the second filter 104 has includes a series arm resonator S_{02} and a parallel arm resonator P_{02} . In this branching filter, the series arm resonators S_{01} and S_{02} and the parallel arm resonators P_{01} and P_{02} are each formed of defined by a surface acoustic wave resonator. That is, by using a surface acoustic wave filter composed of including two surface acoustic wave resonators connected to each other, the first filter 103 and the second filter 104 are each formed provided.

In addition, the first filter 103 has a passband that is lower than that of the second filter 104 and is used as a transmission filter. On the other hand, the second filter 104 is used as a reception filter.

Furthermore, in the branching filter described in the patent document 1 Japanese Unexamined Patent Application

Publication No. 5-167388, inductance elements and capacitor elements (not shown) are connected in the first filter 103 and the second filter 104 so as to achieve matching therebetween.

On the other hand, in the following patent document 2, inJapanese Unexamined Patent Application Publication No. 2-37815, a surface acoustic wave device is disclosed in which electrodes are formed-provided on a piezoelectric substrate, a structure to improve temperature properties has been disclosed which is obtained by forming and a SiO₂ film having a polarity of a temperature coefficient of frequency opposite to that of a piezoelectric single crystal forming the piezoelectric substrate is provided to improve temperature properties.

Patent Document 1: Japanese Unexamined Patent Application
Publication No. 5-167388

Patent Document 2: When the branching filter 101

described in Japanese Unexamined Patent Application

Publication No. 2-37815

Disclosure of Invention

Theidentally,—5-167388 is used as a branching filter used—in a communication apparatus in which the spacing between the passband of a transmission filter and the passband of a reception filter is extremely small, when the branching filter 101 described in the patent document 1 is used,—since the temperature properties of the first filter 103 and that of the second filter 104 are not—insufficient, specification properties may not be satisfied in a desired service temperature range—in some cases. In this case, the

specification properties represent the frequency properties, such as the in-band loss and the amount of attenuation, in the first filter 103 and the second filter 104 of the branching filter 101.

In addition, in the application as described above, when a SiO₂ film is provided only formed on a piezoelectric substrate in order to improve the temperature properties as is the case of the patent document disclosed in Japanese

Unexamined Patent Application Publication No. 2-37815, it has been is difficult to sufficiently ensure the specification properties of the branching filter.

In particular, even when a branching filter is used having a provided which has a small temperature coefficient of frequency by forming a due to the SiO₂ film, for example, in the case of when a PCS communication system in which the passband at the transmission side is 1,850 MHz to 1,910 MHz, the passband at the reception side is 1,930 MHz to 1,990 MHz, and an amount of attenuation of 42 dB or more must be ensuredprovided in the passband of the other side filter, there has been a problem in that the specification properties cannot be satisfied.

That is, when the thickness of a SiO_2 film is increased in order to decrease the temperature coefficient of frequency, although the temperature coefficient of frequency is close to zero, by the increase in film thickness of the

SiO₂ film, causes a decrease in the electromechanical coefficient—is decreased, and as. As a result, the band width is inevitably decreased.

In addition, as a filter forming this type branching filter, a ladder filter has been widely is commonly used. As a to define this type of branching filter. A method for broadening the band width of a ladder filter, a method for broadening the band width toward a low frequency side has been is known in which the inductance of an inductance element is increased which is connected in series to a parallel arm resonator forming to define the ladder filter is increased. This method is an effective method for broadening the band width in the first filter 103 of the branching filter having a relatively low passband.

However, in the second filter 104 side having a relatively high passband, the amount of attenuation at a low frequency side, that is, the amount of attenuation in the passband of the other side filter, i.e., the filter 103, is degraded, and as. As a result, this the method described above cannot be used.

In addition, as—a method for broadening the passband of the second filter 104 of the branching filter having a relatively high passband toward a high frequency side, a method for broadening the band width may be mentioned provided in which inductance elements are added in

parallel to the series arm resonators of the ladder filter. However, by with this method, the inductance elements thus added for broadening the passband of the ladder filter to a high frequency side cause the mutual induction therebetween, and as _. As a result, it is difficult to ensure sufficient attenuation properties.

In a branching filter which is required tomust have a sufficient passband and sufficient attenuation properties, by simply decreasing the temperature coefficient of frequency TCF, it has been is very difficult to satisfactorily obtain the necessary passband width and amount of attenuation in a the desired service temperature range.

In consideration of the conventional techniques

described above, an object

SUMMARY OF THE INVENTION

embodiments of the present invention is to provide a branching filter and a surface acoustic wave device suitably used therein, the. The branching filter capable of ensuringprovides a sufficiently large band width and amount of attenuation in a desired service temperature range, even when being—used in a communication apparatus in which the spacing between the two passbands is small.

The A branching filter according to a preferred

embodiment of the present invention comprises includes a first filter withhaving a relatively low passband, having and a first temperature property-improvement thin film, and a second filter withhaving a relatively high passband, having and a second temperature property-improvement thin film, in which the thickness of the first temperature property-improvement thin film is different from that of the second temperature property-improvement thin film secuch that the temperature coefficient of frequency of the first filter is largergreater than that of the second filter.

In accordance with one aspect of the branching filter according to the present invention, the The first filter and the second filter are preferably defined by surface

The first filter and the second filter are formed of surface acoustic wave filters.

acoustic wave filters.

In accordance with another aspect of the branching filter according to the present invention, the first filter and the second filter are preferably piezoelectric thin-film resonance filters.

In accordance with another aspectEach of the branching filter according to the present invention, the surface acoustic wave filters are each preferably formed using a piezoelectric substrate composed made of a LiTaO3 substrate or a LiNbO3 substrate, and each of the first and the second

temperature property-improvement thin films are $\frac{\text{each}}{\text{preferably}}$ formed of a SiO_2 film provided on the piezoelectric substrate.

In accordance with another aspect of the branching filter according to the present invention, the The thickness of the SiO₂ film provided for the first filter is larger preferably greater than that of the SiO₂ film provided for the second filter.

In accordance with another aspect of the branching filter according to the present invention, when when the wavelength of the first filter is represented by $\lambda 1$, the thickness of the SiO₂ film of the first filter is set preferably in the range of about 0.18 $\lambda 1$ to about 0.38 $\lambda 1$.

In accordance with another aspect of the branching filter according to the present invention, when when the wavelength of the second filter is represented by $\lambda 2$, the thickness of the SiO₂ film provided on the second filter is set preferably in the range of about 0.08 $\lambda 2$ to about 0.28 $\lambda 2$.

In accordance with another aspectEach of the branching filter according to the present invention, the first filter and the second filter are preferably ladder filters each having including series arm resonators and parallel arm resonators.

In accordance with another aspect of the branching filter according to the present invention, at At least one

inductance element <u>is preferably</u> connected in series to one of the parallel arm resonators of the ladder filter <u>forming</u>defining the first filter <u>is further provided</u>.

In accordance with another aspect of the branching filter according to the present invention, atAt least one inductance element is preferably connected in parallel to one of the series arm resonators of the ladder filter forming defining the second filter is further provided.

In accordance with another aspect of the branching filter according to the present invention, the The first filter and the second filter are formed preferably provided on respective piezoelectric substrates and are formed as defined by respective chip components.

<u>embodiment</u> of the <u>branching filter according to the present</u> invention, the first filter and the second filter are <u>formed</u> using preferably provided on the same piezoelectric substrate and are collectively <u>formed asdefined by</u> a single chip component.

A surface acoustic wave filter according to preferred embodiments of the present invention is a surface acoustic wave filterpreferably used as a reception filter of a branching filter, in which the surface acoustic wave filter is formed soconfigured such that the temperature coefficient of frequency thereof is positive with respect to the change

in temperature.

In accordance with one aspect of the A surface acoustic wave filter according to another preferred embodiment of the present invention, includes a piezoelectric substrate composedmade of a LiTaO3 or a LiNbO3 substrate, electrodes formed provided on the piezoelectric substrate, and a temperature property-improvement thin film of a SiO2 film formed arranged so as to cover the electrodes on the piezoelectric substrate are provided, and when the wavelength determined by an electrode cycle is represented by λ , the thickness of the SiO2 film is set—in the range of about 0.3 λ to about 0.38 λ so as to have a positive temperature coefficient of frequency with respect to the change in temperature.

In the branching filter of the present invention, the The thicknesses of the temperature property-improvement thin films of the first and the second filters are preferably different from each other so such that the temperature coefficient of frequency of the first filter having a relatively low passband is largergreater than that of the second filter. Hence Thus, when the spacing in frequency between the passband of the first filter and that of the second filter is small, in the first filter having a relatively low passband, the variation in frequency at a high frequency side of the passband in the first filter

having a relatively low passband is increased, and as. As a result, a the production yield may be degraded in some cases.decreased. However, according to preferred embodiments of the present invention, in the first filter, the change in frequency-temperature properties at a high frequency side of the passband is decreased, and in the second filter, the change in temperature properties at a low frequency side of the passband can be is decreased. Hence Thus, over a desired service temperature range, sufficient passband width and amount of attenuation can be ensured is achieved.

Hence Thus, according to preferred embodiments of the present invention, as a branching filter used for application applications in which the spacing between the reception transmission side frequency and the reception side frequency is small, a branching filter that is capable of satisfying sufficient specification properties over a desired service temperature range can even be is provided.

When the first and the second filters are each formed of defined by a surface acoustic wave filter, the branching filter filter according to preferred embodiments of the present invention can be miniaturized.

As is the case described above, when When the first filter and the second filter are each formed of defined by a piezoelectric thin-film resonator filter, the branching

filter can be miniaturized.

When the surface acoustic wave filter is formed using includes a piezoelectric substrate composed made of a LiTaO3 or a LiNbO3 substrate, and the first and the second temperature property-improvement thin films are SiO2 films formed provided on the piezoelectric substrate, the temperature properties can be are effectively improved by with a simple structure.

When the thickness of the SiO_2 film provided for the first filter is <u>largergreater</u> than that of the SiO_2 film provided for the second filter, by simply changing the thicknesses of the SiO_2 films, the temperature properties of the first and the second filters can be easily adjusted.

When the thickness of the SiO_2 film of the first filter is set—in the range of about 0.18 $\lambda 1$ to about 0.38 $\lambda 1$, the frequency-temperature properties of the first filter can beare effectively improved.

In addition, when the thickness of the SiO_2 film provided for the second filter is set—in the range of about 0.08 $\lambda 2$ to about 0.28 $\lambda 2$, the <u>frequency-temperature</u> coefficient of frequency of properties of the second filter can be are effectively improved.

When the first and the second filters are formed of defined by ladder filters each having including series arm resonators and parallel arm resonators, by using ladder

filters that are commonly used for this type of band filter, thea branching filter according to preferred embodiments of the present invention can be formed provided.

When at least one inductance element connected in series to one of the parallel arm resonators of the ladder filter forming defining the first filter is further provided, the first filter can be matched with the second filter.

As is the case described above, when at least one inductance element is connected in parallel to one of the series arm resonators of the ladder filter forming defining the second filter, the second filter can be easily matched with the first filter.

When the first and the second filters are provided on respective piezoelectric substrates and are formed as defined by respective chip components, the structures configurations of the first and the second filters can be are easily optimized.

In addition, when the first and the second filters useare provided on the same piezoelectric substrate and are collectively formed as defined by a single component, thea branching filter filter according to preferred embodiments of the present invention can be miniaturized.

Since the surface acoustic wave filter <u>according to</u>

<u>preferred embodiments</u> of the present invention is <u>preferably</u>

used as a transmission filter of a branching filter and is

formed soconfigured such that the temperature coefficient of frequency is positive with respect to the change in temperature, even when an electrical power is supplied at a high frequency side of the passband, the degradation in insertion loss is not likely to occur. Hence Thus, an optimum surface acoustic wave filter as a transmission filter of a branching filter can be provided.

In particular, in the case in which when the surface acoustic wave filter includes a piezoelectric substrate composed made of a LiTaO3 or a LiNbO3 substrate, electrodes formedprovided on the piezoelectric substrate, and a temperature property-improvement thin film of a SiO₂ film formedarranged so as to cover the electrodes on the piezoelectric substrate, and in which when the wavelength determined by an electrode cycle is represented by λ , the thickness of the SiO2 film is setpreferably in the range of about 0.3 λ to about 0.38 λ so as to have a positive temperature coefficient of frequency with respect to the change in temperature, the temperature coefficient of frequency TCF of the surface acoustic wave ean be made is positive, and the temperature coefficient of frequency of the branching filter can be decreased as a whole is decreased.

Brief Description of the Drawings

+ Other features, elements, steps, advantages and

characteristics of the present invention will become more
apparent from the following detailed description of
preferred embodiments thereof with reference to the attached
drawings.

BRIEF DESCRIPTION OF THE DRAWINGS

____Fig. 1] Fig. 1 is a circuit diagram showing a circuit structure of a branching filter of one embodiment according to a preferred embodiment of the present invention.

[Fig. 2] Fig. 2 is a view illustrating the change in frequency properties of a second filter of a branching filter, the change being caused by the change in temperature.

[Fig. 3]

Fig. 3 is a view illustrating the frequency properties of first and second filters of a branching filter.

[Fig. 4] Figs. 4(a) and 4(b) are schematic views showing the structures of a first and a second filter, respectively, used in a branching filter of a firstpreferred embodiment of the present invention.

[Fig. 5] Fig. 5 is a view showing the positive change in temperature dependence of a surface acoustic wave device when the thickness of a SiO₂ film is changed.

[Fig. 6] Fig. 6 is a plan view showing an electrode structure of a surface acoustic wave resonator forming the

surface acoustic wave filter used in the firsta preferred embodiment. [Fig. 7] of the present invention.

Fig. 7 is a view showing the change in frequency properties of a first filter suppressed in example 1, the change being caused by the change in temperature. [Fig. 8] Fig. 8 is a view showing the change in frequency properties of a second filter suppressed in example 1, the change being caused by the change in temperature. [Fig. 9] Fig. 9 is a view showing the change in electromechanical coefficient of a surface acoustic wave device when the thickness of a SiO₂ filter is changed. [Fig. 10] Fig. 10 is a view showing the change in frequency properties of a first filter formed in according to example 2, the change being caused by the change in temperature. [Fig. 11] Fig. 11 is a view showing the change in frequency properties of a second filter formed in according to example 2, the change being caused by the change in temperature. [Fig. 12] Fig. 12 is a schematic plan view illustrating a ladder filter used in a surface acoustic wave branching filter of an experimental example according to a preferred embodiment of the present invention. [Fig. 13] Fig. 13 is a view showing a circuit structure

of the ladder filter shown in Fig. 12.

[Fig. 14] Fig. 14 is a surface cross-sectional view
illustrating a showing a piezoelectric thin-film resonator
forming a partdefining a portion of the ladder filter shown
in Fig. 12.
[Fig. 15] Fig. 15 is a schematic front cross-sectional
view illustratingshowing another example of a piezoelectric
thin-film resonator.
[Fig. 16]Fig. 16 is a schematic front cross-sectional
view illustratingshowing still another example of a
piezoelectric thin-film resonator.
[Fig. 17]Fig. 17 is a circuit diagram illustrating one
example of a conventional branching filter.
Reference Numerals
DETAILED DESCRIPTION OF PREFERRED EMBODIMENTS
Fig. 1is-a view showing a circuit structure of a
branching filter according to a first preferred embodiment
of the present invention.
A branching filter 1 according to this
preferred embodiment includes an input terminal 3 of an
antenna terminal
3··· input terminal
11··· first-filter
S11 to S13 · · · series arm resonator

— P11, P12 parallel arm resonator
P21 to P24 ··· parallel arm resonator
- L22 inductance element
31··· piezoelectric substrate
electrode
33 first temperature property improvement thin film
41··· piezoelectric substrate
electrode
substrate
53 · · · insulating film
54··· lower electrode
55 piezoelectric thin film
61 ladder-filter
62···diaphragm
64, 66 series arm resonator

----67 ··· upper electrode

68 lower electrode 69 upper electrode 70 ··· upper electrode 71 ··· piczoelectric thin-film resonator 72 substrate 72a penetrating hole Best Mode for Carrying Out the Invention Fig. 1 is a view showing a circuit structure of a branching filter according to a first-embodiment of the present invention. A branching filter 1 of this embodiment has an input terminal 3 belonging to an antenna 2. To the input terminal 3, a first filter 11 and a second filter 12 are connected. The first filter 11 has a relatively low passband, and the second filter 12 has a relatively high passband. That is,

In addition, in this <u>preferred</u> embodiment, the first filter 11 is <u>formed ofdefined</u> a ladder filter having including series arm resonators S11 to S13 and parallel arm resonators P11 and P12. Furthermore, between the parallel arm resonators P11 and P12 and the eartha

transmission filter and is a reception filter, respectively.

in the branching filter 1, the first filter 11 is a

transmission filter and the second filter 12 are a

ground potential, inductance elements L11 and L12 are connected, respectively.

In addition, between the input terminal 3 and the series arm resonator S11, a capacitor element C11 is connected.

The second filter 12 has a ladder type circuit structure as is configuration similar to the first filter 11. That is, the second filter 12 has includes a plurality of series arm resonators S21 to S23 and a plurality of parallel arm resonators P21 to P24. In addition, an inductance element L22 is connected in parallel to the series arm resonator S23.

Between the input terminal 3 and an input terminal 12a of the second filter 12, an inductance element L21 is connected. Between the earthground potential and a connection point provided between the input terminal 3 and the inductance element L21, a capacitor element C21 is connected. Between the earthground potential and a connection point provided between the input terminal 12a and the inductance element L21, a capacitor element C22 is connected.

The capacitor element C-11 connected to the first filter 11 is matching element. In addition, the inductance element L21 and the capacitor elements C21 and C22 are provided arranged to match the second filter 12 with the

first filter 11. That is, the inductance element L21 and the capacitor elements C21 and C22 formdefine a matching circuit.

The feature of In the branching filter 1 of according this preferred embodiment—is that, the first filter 11 and the second filter 12 have include a first temperature property-improvement thin film and a second temperature property-improvement thin film, respectively, and the thicknesses thereof are different from each other so such that a temperature coefficient of frequency TCF of the first filter 11 is larger greater than that of the second filter 12.

Hence, by Thus, with the structure described above, sufficient specification properties in a service temperature range can be are obtained. Hereinafter, the details will be described.

In a surface acoustic wave filter and a piezoelectric thin-film resonance filter, fine electrodes or very thin electrode films are <u>formedprovided</u>, and as a result, the electrical resistance is relatively high. <u>HenceThus</u>, when the environmental temperature is increased, the resistivity is changed, and as. As a result, there has been a problem in that a-filter loss is increased. The change in properties of a filter caused by the change in temperature will be described with reference to Fig. 2.

Fig. 2 shows general frequency properties of this type

of filter. A solid line A shown in Fig. 2 indicates the frequency property, and solid lines A1 to A3 show the states of the change in the frequency property A, which is caused by the change in temperature, by enlarging the scale of the vertical axis indicating the insertion loss. The solid lines A1, A2, and A3 indicate the properties in the passband at approximately -30°C, 25°C, and +85°C, respectively, the properties being shown byusing enlarged values.

When the shift of the central frequency caused by the change in temperature is assumed not to occur at all, at a low frequency side of the passband, the degradation in loss caused by the increase in temperature is equivalent to that obtained when the frequency is shifted to a high frequency side as shown by an arrow B1 in Fig. 2, and at a high frequency side, the degradation is equivalent to that obtained when the frequency is shifted to a low frequency side as shown by an arrow B2.

Furthermore, in a branching filter in which a first filter having a relatively low passband and a second filter having a relatively high passband are provided in combination, when the spacing between the respective frequencies is extremely small, as the properties of a branching filter shown in Fig. 3, the temperature dependence of frequency at a high frequency side (indicated by an arrow C) of the passband of the first filter may be decreased, and

as for the second filter, the temperature dependence of frequency at a low frequency side of the second filter, (indicated by an arrow D) may be decreased. ByWith the structure as described above, the variation in frequency of the branching filter, as a whole which occurs induring production, can be are decreased as a whole.

In <u>preferred embodiments of</u> the present invention, the amount of change in frequency caused by the change in temperature is decreased at the central frequency of the second filter having a relatively high passband as compared to that of the first filter having a relatively low passband, so—such that the variation in frequency of the branching filter as a whole is decreased—as—a whole.

In this specification of the present invention, the case in which the temperature coefficient of frequency is small indicates that, for example, -20 ppm is small relative to -10 ppm, and -5 ppm is small relative to +5 ppm. That is, it is to be elearly understood that a small temperature coefficient of frequency is not determined by the absolute value thereof, and that as the TCF is decreased toward a negative value side, the temperature coefficient of frequency is ealled referred to as small. Accordingly, "the temperature coefficient of frequency is larger" indicates that the temperature coefficient of frequency TCF has a more positive value.

Figs. 4(a) and 4(b) are schematic front cross-sectional views of the first filter 11 and the second filter 12, respectively, of the branching filter 1 according to the above-described preferred embodiment.

The first filter 11 shown in Fig. 4(a) is a filter having a relatively low passband and, in this <u>preferred</u> embodiment, is <u>formed of defined by</u> a surface acoustic wave filter. The first filter 11 has the structure in whichincludes electrodes 32, such as an IDT electrode are formed electrodes, which are provided on a piezoelectric substrate 31. In addition, a first temperature property-improvement thin film 33 is <u>formedarranged</u> so as to cover the electrodes 32.

In this <u>preferred</u> embodiment, the piezoelectric substrate 31 is <u>formed of preferably</u> a LiTaO₃ substrate. In addition, the electrodes 32 <u>are formed of electrodes</u> preferably are primarily <u>composed made</u> of Cu, and the first temperature property-improvement thin film 33 is <u>formed made</u> of SiO₂.

The second filter 12 shown in Fig. 4(b) has the structure in which includes electrodes 42, such as an-IDT electrode are formed electrodes, which are provided on a piezoelectric substrate 41. A second temperature property improvement thin film 43 is formedarranged so as to cover the electrodes 42. Also in In the second filter 12, the

piezoelectric substrate 41 is formed of a LiTaO₃ substrate, the electrodes 42 are preferably primarily composed of include Cu, and the second temperature property-improvement thin film 43 is formed made of SiO₂.

In this <u>preferred</u> embodiment, with respect to LiTaO₃ having a negative temperature coefficient of frequency, the temperature property-improvement thin films 33 and 43, which are provided for improving the temperature properties, are each <u>formedmade</u> of SiO₂ having a positive temperature coefficient of frequency. In addition, as <u>ean be seen</u> <u>fromshown in</u> Figs. 4(a) and 4(b), the thickness of the first temperature property-improvement thin film 33 provided for the first filter 11 having a relatively low passband is <u>formed largergreater</u> than that of the temperature property-improvement thin film 43 provided for the second filter 12 having a relatively high passband.

Fig. 5 is a view showing the relationship between the temperature coefficient of frequency TCF and the thickness of a SiO_2 film formedarranged so as to cover the electrodes of a surface acoustic wave device.

As can be seen from shown Fig. 5, as the thickness of the SiO₂ film is increased, increases, the temperature coefficient of frequency TCF is shifted to a positive side. That is, the temperature coefficient of frequency becomes larger increases.

As shown in Figs. 4(a) and 4(b), in this preferred embodiment, the thickness of the first temperature propertyimprovement thin film 33 of the first filter 11 having a relatively low passband is relatively large, and the thickness of the temperature property-improvement thin film 43 of the second filter 12 having a relatively high passband is relatively small. HenceThus, the temperature coefficient of frequency of the first filter 11 is made large, increased, and the temperature coefficient of frequency of the second filter 12 is made small.decreased. Accordingly, in the branching filter as a whole, the temperature dependence of frequency is suppressed, and the variation in frequency ean beis decreased. In other words, the specification property in a desired service temperature range can be sufficiently is ensured. The details will be described with reference to particular experimental examples.

Example 1+

The branching filter 1 of the <u>preferred</u> embodiment shown in Fig. 1 was formed by the following procedure. The first filter 11 is a transmission filter, and the second filter 12 is a reception filter. The branching filter 1 is a filter used in a system in which the filter band of the transmission side is <u>about 1,850 toMHz</u> to about 1,910 MHz, and the passband of the reception filter is <u>about 1,930 MHz</u>

to about 1,990 MHz.

In the above-described system, the frequency spacing between the passband of the transmission filter and that of the reception filter is very small, such as about 20 MHz. HenceThus, both of the first filter and the second filter are required to have steep filter properties, and in. In addition, both of the first filter and the second filter are required to have superior temperature dependence of frequency—is also necessary.

In particular, since the first filter 11 as defining the transmission filter must use the passband of the reception filter 12 as an attenuation band, the steepness at a high frequency side of the passband of the first filter 11 must be enhanced, and in. In addition, improvement in temperature dependence at a high frequency side of the passband is strongly required.

On the other hand, since the second filter 12 as the reception filter must use the passband of the first filter 11 as an attenuation periodband, in addition to the enhancement of the steepness at a low frequency side of the passband of the second filter 12, improvement in temperature dependence at a low frequency side of the passband is also required. As the series arm resonators and the parallel arm resonators formingdefining the first filter 11 and the second filter 12, surface acoustic wave resonators having

the electrode structure shown in Fig. 6 were used. An electrode structure 151 shown in Fig. 6 has includes an IDT electrode 5244 and reflectors 5345 and 5446 provided at two sidedboth sides of the IDT electrode 52.44. The electrode structure 151 is formedprovided on a piezoelectric substrate, sesuch that one surface acoustic wave resonator is formed.provided. As shown in Fig. 1, the first filter 11 has includes the series arm resonators S11 to S13 and the parallel arm resonators P11 and P12, and the second filter 12 has includes the series arm resonators S21 to S23 and the parallel arm resonators P21 to P24. These series arm resonators S11 to S13, S21 to S23 and parallel arm resonators P11, P12, P21 to P24 are each formed of defined by the above-described surface acoustic wave resonator.

In addition, the first filter 11 and the second filter 12 have the circuit structures shown in Fig. 1. Electrode parameters of the individual resonators of the first and the second filters are shown in Tables 1 and 2 below.

{Table 1}

	S 1 1	P 1 1	S 1 2	P 1 2	S 1 3
DUTY	0.55	0.55	0.55	0.55	0.55
NUMBER OF STAGES	2	1	3	1	2
NUMBER of ELECTRODE FINGER PAIRS	200	120	200	120	200
CROSS WIDTH (μM)	40	100	40	100	40
NUMBER OF ELECTRODE FINGERS OF REFLECTOR	20	20	20	20	20
WAVELENGTH (μm)	2.0275	2.0682	2.0152	2.0682	2.0275

{Table 2}

	P 2 1	S 2 1	P 2 2	S 2 2	P 2 3	S 2 3	P 2 6
DUTY	0.55	0.55	0.55	0.55	0.55	0.55	0.55
NUMBER OF STAGES	1	2	1	2	1	1	1
NUMBER OF ELECTRODE FINGER PAIRS	40	120	100	120	100	120	40
CROSS WIDTH (μM)	40	40	40	40	40	40	40
NUMBER OF ELECTRODE FINGERS OF REFLECTOR	20	20	20	20	20	20	20
WAVELENGTH (μm)	1.9620	1.8890	1.9620	1.8890	1.9620	1.9300	1.9620

	P 2 1	S 2 1	P 2 2	S 2 2	<u>P 2 3</u>	S 2 3	P 2 4
DUTY	0.55	0.55	0.55	0.55	0.55	0.55	0.55
NUMBER OF STAGES	1	2	1	2	1	1	1
NUMBER OF ELECTRODE FINGER PAIRS	40	120	100	120	100	120	40
CROSS WIDTH (µm)	<u>40</u>	<u>40</u>	<u>40</u>	<u>40</u>	<u>40</u>	<u>40</u>	<u>40</u>
NUMBER OF ELECTRODE FINGERS OF REFLECTOR	20	20	20	20	20	20	20
WAVELENGTH (µm)	1.9620	1.8890	1.9620	1.8890	1.9620	1.9300	1.9620

The electrostatic capacitance of the capacitor element C11 of the first filter 11 was set to about 5 pF. In addition, the inductances—inductance of each of the inductance elements L11 and L12 werewas set to about 3 nH and 3 nH, respectively. Furthermore, the inductance of the inductance element L21 of the second filter 12 was set to about 3 nH, the inductance of the inductance element L22 was set to about 3 nH, the capacitance of the capacitor element C21 was set to about 2 pF, and the capacitance of the

capacitor element C22 was set to about 2.5 pF.

In this example, the first filter 11 and the second filter 12 are collectively formed as defined by a single chip component using the same 36° X propagating LiTaO3 substrate. That is, on one LiTaO3 substrate, a first circuit structure is provided. Since the above-described filters are formed as defined by a single chip component, the branching filter 1 can be is miniaturized.

The electrodes preferably are each formed of an electrode primarily composed made of Cu, and as described above, in the first filter 11 and the second filter 12, the first temperature property-improvement thin film 33 composed made of SiO2 and the second temperature propertyimprovement thin film 43 composed made of SiO2 are formedprovided, respectively (see Figs. 4(a) and 4(b)). The formation of the SiO₂ film was performed by sputtering. In addition, the thickness of the SiO2 film as the first temperature property-improvement thin film 33 of the first filter 11 was set to about 0.35 λ 1, that is, about 715 nm, when the average wavelength of the first filter 11 was represented by $\lambda 1$. The average wavelength is an average value of the wavelengths of the parallel arm resonators and the wavelengths of the series arm resonators.

On the other hand, in the second filter 12, the thickness of the SiO_2 film as the second temperature

property-improvement thin film 43 was set to about 0.25 $\lambda 2$, that is, 483 nm, when the average wavelength was represented by $\lambda 2$.

The frequency-temperature properties of the first filter 11 and the second filter 12 of the branching filter 1 formed as described above are shown in Figs. 7 and 8, respectively.

In Figs. 7 and 8, properties shown in a lower side are important partsportions of the properties shown in an upper side and are shown by an enlarging theenlarged scale of the vertical axis. In addition, in Figs. 7 and 8, the frequency properties at temperatures of approximately -30°C, 25°C, and 85°C are shown.

Since the second filter 12 is a reception filter, the amount of attenuation must be ensured in the passband of the first filter 11 which is present at a low frequency side of the passband of the second filter 12. Hence Thus, in the frequency properties of the second filter 12 shown in Fig. 8, superior temperature dependence of frequency must be ensured at a low frequency side of the passband.

On the other hand, the amount of increase in loss at a low frequency side of the passband caused by <u>an</u> increase in temperature is equivalent to that of the change obtained when the frequency is shifted to a high frequency side (see Fig. 2). Accordingly, when the temperature coefficient TCF

of the central frequency of the second filter 12 is set to approximately -7 ppm/°C, the amount of frequency shift of the second filter 12 at a low frequency side caused by the change in temperature can be made—is approximately zero.

In addition, as shown in Fig. 7, the first filter 11 is a transmission filter, and the amount of attenuation thereof must be sufficiently increased in the passband of the reception filter which is present at a high frequency side of the passband of the first filter 11, and in particular, a superior temperature dependence of frequency must be ensured at a high frequency side of the passband. As shown in Fig. 2, the amount of increase in loss at a high frequency side of the passband caused by increase in temperature is equivalent to that of the change obtained when the frequency is shifted to a low frequency side. Accordingly, in the first filter 11, when the temperature dependence of the central frequency is selected to be approximately +7 ppm/°C, the amount of frequency shift at a high frequency side ean be made—is approximately zero.

In addition, in-Fig. 9₇ shows the change in electromechanical coefficient of this type of surface acoustic wave filter is shown which is obtained when the thickness of the SiO₂ film is changed. When the thickness of the SiO₂ film is increased, due to the increase in increased mass, the electromechanical coefficient is

decreased. Hence Thus, as a result, it becomes difficult to sufficiently increase the band width of the filter.

Accordingly, in this example, the inductance elements £1£11 and £12 are connected in series to the parallel arm resonators P11 and P12, respectively, of the first filter 11, and hence thus, the band width is increased thereby.

In addition, the inductance element L22 is connected in parallel to the series arm resonator S23 of the second filter 12, so—such that the band width of the second filter 12 is also increased.

As a result, in the branching filter 1 of this example, as described above, the temperature dependence of frequency is decreased to approximately zero as a whole, the variationvariations in frequency properties in a service temperature range is are not liablelikely to occur, and furthermore, the band widths of the respective filters 11 and 12 are sufficiently increased. Hence Thus, in the service temperature range, the specification properties can beare satisfactorily fulfilled obtained.

In this example, as the piezoelectric substrate, the 36° LiTaO₃ substrate was used; however, . However, for example, a LiTaO₃ substrate having another cut angle such as a 42° LiTaO₃ substrate may also be used. Furthermore, a LiNbO₃ substrate may also be used which has been known as a substrate having the effect equivalent to that of a LiTaO₃

substrate.

Furthermore, a material for the electrode is not limited to a material primarily <u>composed of including</u> Cu, and a material primarily <u>composed of including</u> another metal, such as Al, may also be used.

In addition, SiO₂ films are preferably used as the first and the second temperature property-improvement thin films, SiO₂ films are used; however. However, the temperature property-improvement thin films may be formed of another suitable material. Furthermore, the first and the second temperature property-improvement thin films may be formed of materials that are different from each other.

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Example 2+

A branching filter was formed in the same manner as that in example 1. However, in example 2, the thickness of the SiO_2 film as the first temperature property-improvement thin film 33 of provided for the first filter 11 was set to about 0.25 λ 1, that is, about 515 nm, and the thickness of the SiO_2 film provided for the second filter 12 was set to about 0.15 λ 2, that is, about 290 nm. The rest of theremaining structure was the same as that in example 1.

Fig. 10 is a view showing the change in frequency properties of the first filter 11 of example 2 caused by the change in temperature, and Fig. 11 is a view showing the

change in frequency properties of the second filter 12 caused by the change in temperature.

It is understood that the change of the central frequency of the first filter 11 is approximately -7 ppm/°C, and that the change of the central frequency of the second filter 12 is approximately -20 ppm/°C.

At a high frequency side of the passband, since the amount of change in the loss component caused by the increase in temperature works toward a negative side, it is understood that the temperature dependence of frequency of the passband of the first filter 11 shows—is approximately - 14 ppm/°C at a high frequency side.

On the other hand, at a low frequency side of the passband, since the amount of change caused by the increase in temperature is equivalent to that obtained when the frequency is shifted to a high frequency side, the temperature dependence of the frequency properties is decreased to approximately -14 ppm/°C, as is the case of in the first filter 11.

Hence, it is understood that Thus, when the thickness of the SiO₂ film is relatively increased at the first filter 11 side, the temperature dependence at a high frequency side of the passband of the first filter 11 and that at a low frequency side of the passband of the second filter 12 can be madeare approximately equivalentequal to each other. In

example 2, compared to the case of example 1, although the temperature coefficient of frequency is slightly increased, in both the first filter 11 and the second filter 12, temperature dependences which are approximately equally suppressed can be are obtained. Hence Thus, in production, a desired branching filter can be provided by easily combining a transmission filter and a reception filter with each other, both of which have temperature dependences approximately equivalent equal to each other.

In addition, in order to decrease the temperature coefficient of frequency, when the thickness of the SiO2 film is too much increased too much, a problem as shown in Fig. 9 may arise in that the electromechanical coefficient is decreased. In example 2, since appropriate temperature property-improvement effect and electromechanical coefficient can be are obtained, a branching filter having more—superior frequency properties at room temperature can be-is provided. In particular, in example 2, when the thickness of the SiO_2 film as the second temperature property-improvement thin film provided for the second filter is set in the range of about 0.08 λ 2 to about 0.28 λ 2, the temperature dependence of frequency of the second filter can be is improved at a low frequency side. In addition, when the thickness of the SiO2 film as the first temperature property-improvement thin film provided for the first filter

is set in the range of <u>about 0.18 λ 1</u> to <u>about 0.38 λ 1</u>, the temperature dependence of frequency of the first filter as a transmission filter <u>can be is</u> improved at a high frequency side of the passband.

In the <u>preferred</u> embodiment described above, the first filter 11 and the second filter 12 are each <u>formed of</u> <u>defined by</u> a surface acoustic wave filer; <u>however</u>. <u>However</u>, the first filter 11 and the second filter 12 are not limited to a surface acoustic wave filter, and may be formed using other <u>suitable</u> filters. That is, an appropriate filter having a temperature property-improvement thin film may be used as the first and the second filters. As the filters described above, for example, a piezoelectric thin-film resonator filter may be mentioned preferably be used.

Fig. 12 is schematic plan view showing a ladder filter formeddefined by using a plurality of piezoelectric thin-film resonator filters, and the circuit structure of this ladder filter is shown in Fig. 13.

In addition, Fig. 14 is a front cross-sectional view showing one piezoelectric thin-film resonator forming defining the ladder filter.

As shown in Fig. 14, a piezoelectric thin-film resonator 51 is formed using a includes a substrate 52 having a recess portion 52a openedwhich is open to the upper side. An insulating film 53 is laminated so as to cover

this recess portion 52a. Then, on the insulating film 53, a lower electrode 54, a piezoelectric thin film 55, and an upper electrode 56 are laminated, so—such that a diaphragm is formed. The piezoelectric thin film 55 is formed preferably made of an appropriate piezoelectric material, such as titanate zirconate lead ceramic, ZnO, or AlN. electrodes 54 and 56 are formedpreferably made of an appropriate metal or alloy, such as Al or Ag. The polarization axes of the piezoelectric thin film 55 are aligned in the thickness direction. Hence Thus, when a voltage is applied to the piezoelectric thin film 55 from the electrodes 54 and 56, the piezoelectric thin film 55 is allowed to oscillate. oscillates. In this case, since the laminate structure is provided on the recess portion 52a of the substrate 52, the oscillation of the piezoelectric thin film 55 is not inhibited, and as—. As a result, resonance properties which can be usedare suitable for use in a high frequency band is are obtained. The substrate 52 may be formed using made of an appropriate insulating or semiconductor material, such as a Si substrate. In addition, the insulating film 53 may also be formed using made of an insulating material, such as Al₂O₃, SiO₂, or AlN.

Fig. 12 is a schematic plan view of a ladder filter having a two-stage structure formed using defined by a plurality of piezoelectric thin-film resonators described

In Fig. 12, the piezoelectric thin films are not shown. In a ladder filter 61, a part portion surrounded by a dotted line formsdefines a diaphragm 62. That is, the diaphragm 62 indicates an upper part portion of the recess portion 52a of the piezoelectric thin-film resonator 51_{7} that is, indicates which defines an oscillation part.portion. In this diaphragm 62, two parallel arm resonators 63 and 65 and two series arm resonators 64 and 66 are provided. more particular More particularly, in the ladder filter 61, a lower electrode 68 is provided arranged so as to be connected to the ground potential. In addition, an upper electrode 67 is connected to an input terminal. An upper electrode 69 is connected to the ground potential. In addition, an upper electrode 70 is connected to an output terminal. Hence Thus, the ladder filter having a two-stage structure shown in Fig. 13 is formedprovided.

In the piezoelectric thin-film resonator 51 shown in Fig. 14, the recess portion 52a opened opening to the upper side is provided in the substrate 52; however. However, as shown in Fig. 15, a piezoelectric thin-film resonator 71 may also be used usingwhich includes a substrate 72 having a penetrating hole 72a, the diameter of which is increased increases toward the lower side. In this case, the insulating film 53 is laminated so as to cover the upper opening of the penetrating hole 72a. In addition, on the

insulating film 53, the lower electrode 54, the piezoelectric thin-film 5455, and the upper electrode 56 are laminated, so such that the diaphragm is formed provided.

Furthermore, as shown in Fig. 16, a common electrode 81 may be formed_provided_at the lower side of the insulating film 53 so as to face a pair of lower electrodes 54 with the insulating film 53 provided therebetween. In this case, the upper electrode 56 faces the pair of lower electrodes 54, so such that a pair of resonator portions is formed.provided.

In addition, between the common electrode 81 and the lower electrodes 54, respective capacitors may be formed.provided. As described above, a piezoelectric thin-film resonator incorporating including the capacitors formed of defined by the common electrode 81 and the lower electrodes 54 may be used for forming in the ladder filer described above.

— While the present invention has been described with

— While the present invention has been described with respect to preferred embodiments, it will be apparent to those skilled in the art that the disclosed invention may be modified in numerous ways and may assume many embodiments other than those specifically set out and described above.

Accordingly, it is intended by the appended claims to cover all modifications of the present invention which fall within the true spirit and scope of the invention.